

| Ref # | Hits  | Search Query   | DBs  | Default Operator | Plurals | Time Stamp       |
|-------|-------|--|--|------------------|---------|------------------|
| L21   | 8204  | STI or "shalow trench isolation"   | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 09:57 |
| L22   | 26109 | "chemical mechanical polishing" or<br>(chemical adj mechanical adj<br>polishing)                     | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 09:58 |
| L23   | 40705 | (mask\$3 or pattern\$4) same<br>(trenches or grooves)  | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 09:59 |
| L24   | 7237  | (mask\$3 or pattern\$4) same<br>(trenches or grooves) same (resist<br>or photoresist)                | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 10:50 |
| L25   | 2532  | 21 and 22  | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 10:00 |
| L26   | 450   | 25 and 24  | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 10:50 |
| L31   | 764   | (mask\$3 or pattern\$4) same<br>(trenches or grooves) same (resist<br>or photoresist) same polish\$4 | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 10:51 |
| L32   | 173   | 31 and 21  | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 11:10 |
| L33   | 0     | hoolatz-mark.in.   | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 11:10 |
| L34   | 12    | hollatz-mark.in.   | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 11:11 |
| L37   | 19    | morhard-klaus-dieter.in.   | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 11:12 |
| L38   | 1     | truby-alexander.in.  | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/16 11:13 |